

***Amendments to the Claims***

The listing of claims will replace all prior versions, and listings of claims in the application.

Claims 1-17 (canceled)

18. (Currently Amended) A lithography apparatus comprising:

(a) a source producing a light beam having at least one wavelength within the UV spectrum;

(b) a mask;

(c) a substrate transparent to light in the UV spectrum and disposed in a path of the light beam; and

(d) an array of wire elements on the substrate;

wherein the array of wire elements are divided into wedge-shaped groups of having parallel wire elements therein to polarize incident UV light and output light that is tangentially polarized about an axis at a center of the polarizer ~~with respect to the cylindrical symmetry of the polarizer~~, wherein adjacent wedge-shaped groups are arranged around the axis ~~separated by a boundary extending from a perimeter of the polarizer to a center of the polarizer~~, and wherein the parallel wire elements of each group are non-interlaced.

19. (Previously Presented) The apparatus of claim 18, wherein the elements in said group have a pitch of about one quarter the wavelength of the beam of UV light.

20. (Previously Presented) The apparatus of claim 18, wherein the elements in said group have a pitch between about  $0.1\lambda$  and  $2\lambda$ , where  $\lambda$  is the wavelength of the beam.

21. (Original) The apparatus of claim 18, wherein the elements have a thickness of between about 0.04 and 0.3  $\mu\text{m}$ .

22. (Previously Presented) The apparatus of claim 18, wherein the substrate includes fused silica, calcium fluoride, sapphire, quartz, or magnesium fluoride.

23. (Previously Presented) The apparatus of claim 18, wherein the UV light comprises at least two polarizations and wherein the elements generally reflect most incident light of a first polarization direction and transmit most of the light of a second polarization direction.

24-25. (Canceled)

26. (Previously Presented) A lithographic apparatus for providing an exposure beam along an optical path comprising:

- (a) a wire grid polarizer;
- (b) an illuminator having a pupil; and
- (c) a mask;

wherein the polarizer comprises a substrate that is transparent to ultraviolet (UV) light and an array of elements patterned on the substrate that polarize UV light and produce radially polarized light.

27. (Canceled)

28. (Previously Presented) The apparatus of claim 20, wherein the elements of said group have a pitch between about  $0.1\lambda$  and  $0.5\lambda$ , where  $\lambda$  is the wavelength of the beam.

29. (Previously Presented) The apparatus of claim 20, wherein the elements of said group have a pitch of about one quarter of a wavelength of the UV light.

30. (Previously Presented) The apparatus of claim 20, wherein the elements of said group have a pitch of between about 45 nm and 95 nm.

31. (Previously Presented) The apparatus of claim 18, wherein the elements include aluminum, silver or gold.

32. (Previously Presented) The apparatus of claim 18, wherein the incident UV light is substantially unpolarized.